

INFORMATION DISCLOSURE STATEMENT

Applicant : Hojo et al.
Int. App. : PCT/JP2004/005804
No
Int. Filing : ~~March 21, 2001~~ April 22, 2004
Date
For : POSITIVE PHOTORESIST
COMPOSITION AND METHOD FOR
FORMING RESIST PATTERN
Examiner : Unknown
Art Unit : Unknown

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

Enclosed for filing in the above-identified application is a PTO/SB/08 Equivalent listing 14 references to be considered by the Examiner. Also enclosed are 10 foreign patent references and/or non-patent literature as listed on the Information Disclosure Statement. The relevance of all foreign-language references is that they were cited in the International Search Report during the International Phase of the present application.

This Information Disclosure Statement is being filed within three months of the filing date, and no fee is required. However, the Commissioner is hereby authorized to charge any fees which may be required to Account No. 11-1410.

Respectfully submitted,

KNOBBE, MARTENS, OLSON & BEAR, LLP

Dated:

26 Oct. 2005

By:

Daniel E. Altman

Daniel E. Altman
Registration No. 34,115
Attorney of Record
Customer No. 20,995
(949) 760-0404

INFORMATION DISCLOSURE STATEMENT BY APPLICANT <i>(Multiple sheets used when necessary)</i>	Application No.	Unknown 10/554380	
	Filing Date	Herewith	
	First Named Inventor	Hojo, Takuma	
	Art Unit	Unknown	
SHEET 1 OF 1		Examiner	Unknown
		Attorney Docket No.	SHIGA7.032APC

U.S. PATENT DOCUMENTS					
Examiner Initials	Cite No.	Document Number Number - Kind Code (if known) Example: 1,234,567 B1	Publication Date MM-DD-YYYY	Name of Patentee or Applicant	Pages, Columns, Lines Where Relevant Passages or Relevant Figures Appear
	1	US 2003/0113661 A1	06-19-2003	Uetani et al.	
	2	6,627,381 B1	09-30-2003	Uetani et al.	
	3	US 2002/0068238 A1	06-06-2002	Hada et al.	
	4	6,033,828	03-07-2000	Shimada et al.	

FOREIGN PATENT DOCUMENTS						
Examiner Initials	Cite No.	Foreign Patent Document Country Code-Number-Kind Code Example: JP 1234567 A1	Publication Date MM-DD-YYYY	Name of Patentee or Applicant	Pages, Columns, Lines Where Relevant Passages or Relevant Figures Appear	T ¹
	5	WO 01/73512 A1	04-10-2001	Sumitomo Chem. Co.		Abstract
	6	JP 2002-6501	01-09-2002			
	7	UK 2,356,258 A	05-17-2001	Sumitomo Chem. Co.		
	8	WO 00/46640	08-10-2000	Sumitomo Chem. Co.		Abstract
	9	JP 2003-321520	11-14-2003			
	10	EP 1,357,428 A1	10-29-2003	Nippon Shokumbai Co.		X
	11	JP 2002-241442	08-28-2002	Daicel Chem Ind. Ltd.		Abstract
	12	JP 2002-169292	06-14-2002			
	13	JP 10-268508	10-09-1998			

NON PATENT LITERATURE DOCUMENTS			
Examiner Initials	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ¹
	14	International Search Report from priority PCT application serial no. PCT/JP 2004/005804.	

2019157:vr
102505

Examiner Signature	Date Considered
--------------------	-----------------

*Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

T¹ - Place a check mark in this area when an English language Translation is attached.